

# **DAT110**

# **METHODS FOR ELECTRONIC SYSTEM**

# **DESIGN AND VERIFICATION**

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# **LECTURE 6:**

# **POWER AND ENERGY.**

# **VARIABILITY.**

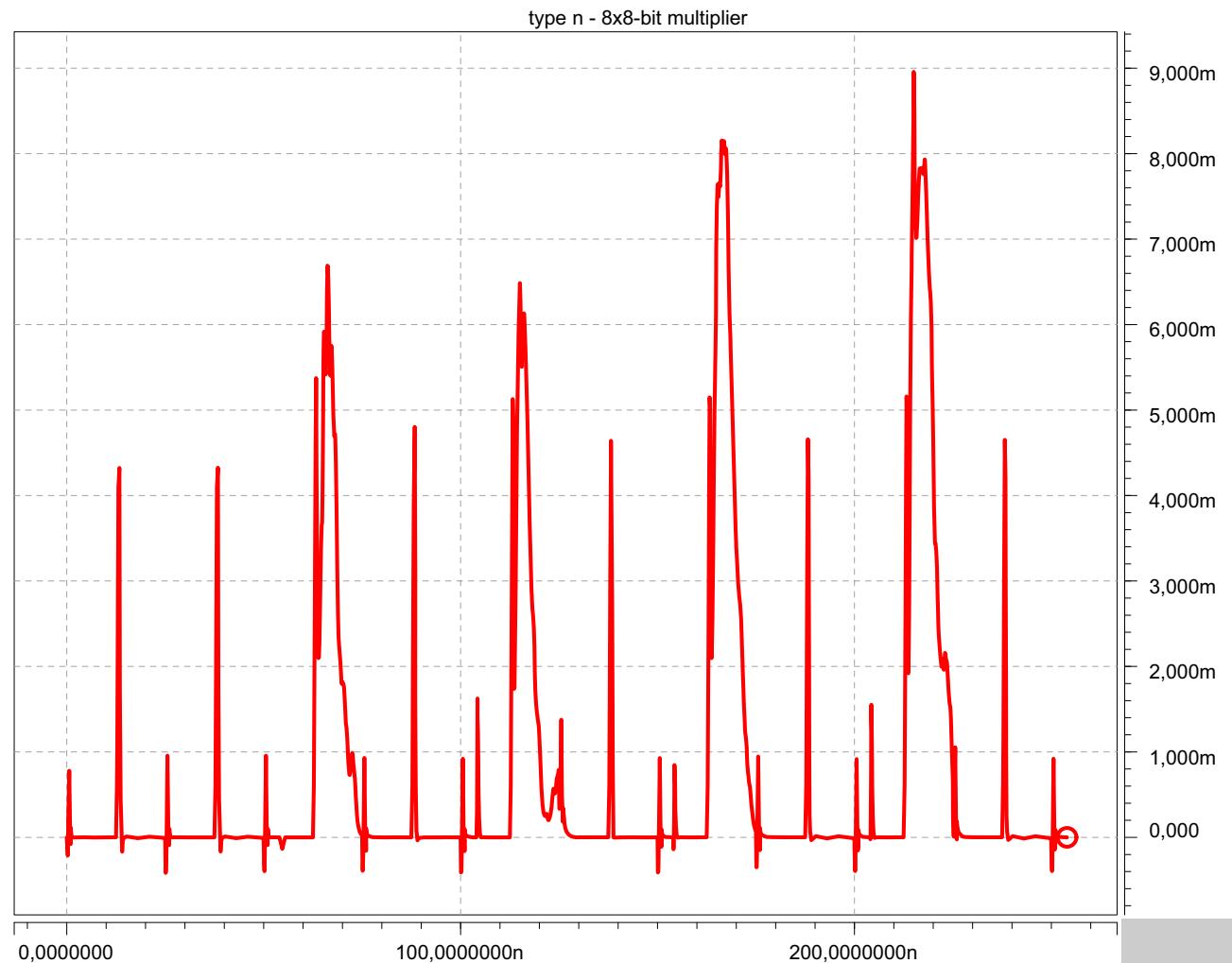
## **BACK TO BASICS - POWER AND ENERGY**

- ◆ Charges  $Q = I \cdot t$  are transported during time  $t$ , thanks to a current  $I$  (which is assumed to be constant!).
- ◆ Energy  $E = Q \cdot V$  is associated with the charges  $Q$  that sit inside an electric field, at a potential  $V$ .
- ◆ Power dissipation  $P = E/t$  is energy  $E$  expended during time  $t$ .

$$\◆ P = \frac{E}{t} = \frac{(Q \cdot V)}{t} = \frac{((I \cdot t) \cdot V)}{t},$$

which becomes  $P = I \cdot V$ ,  
when current and voltage are constant.

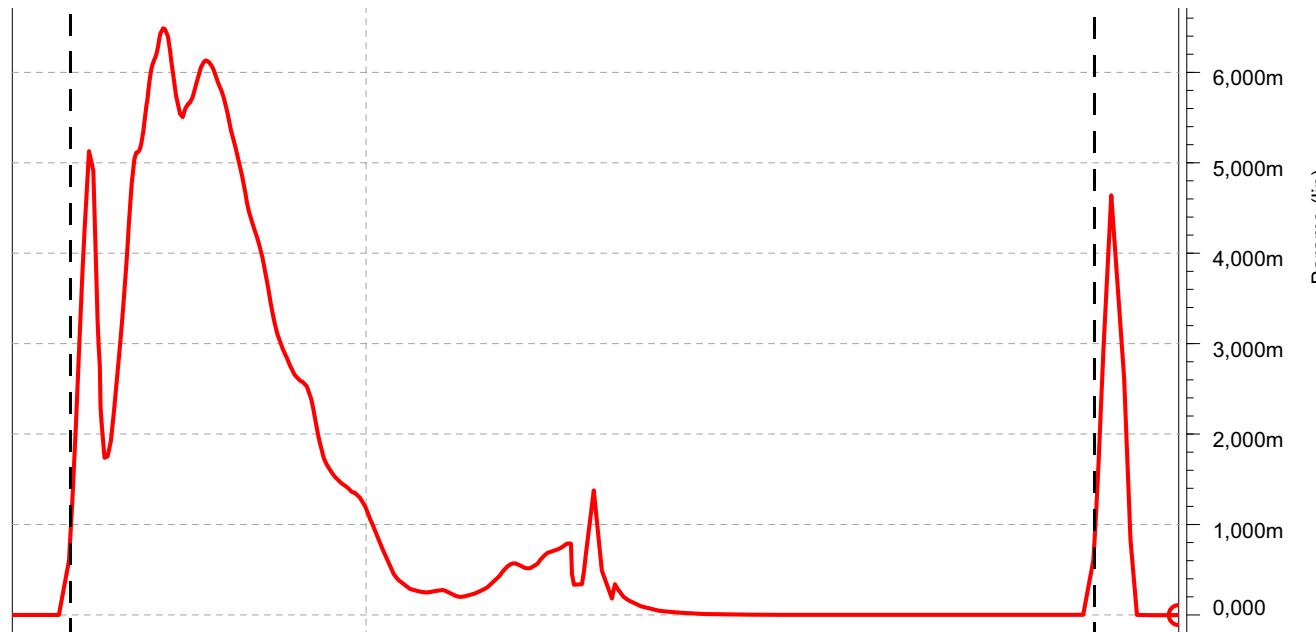
# CURRENT VARIES (OVER 10 CYCLES)



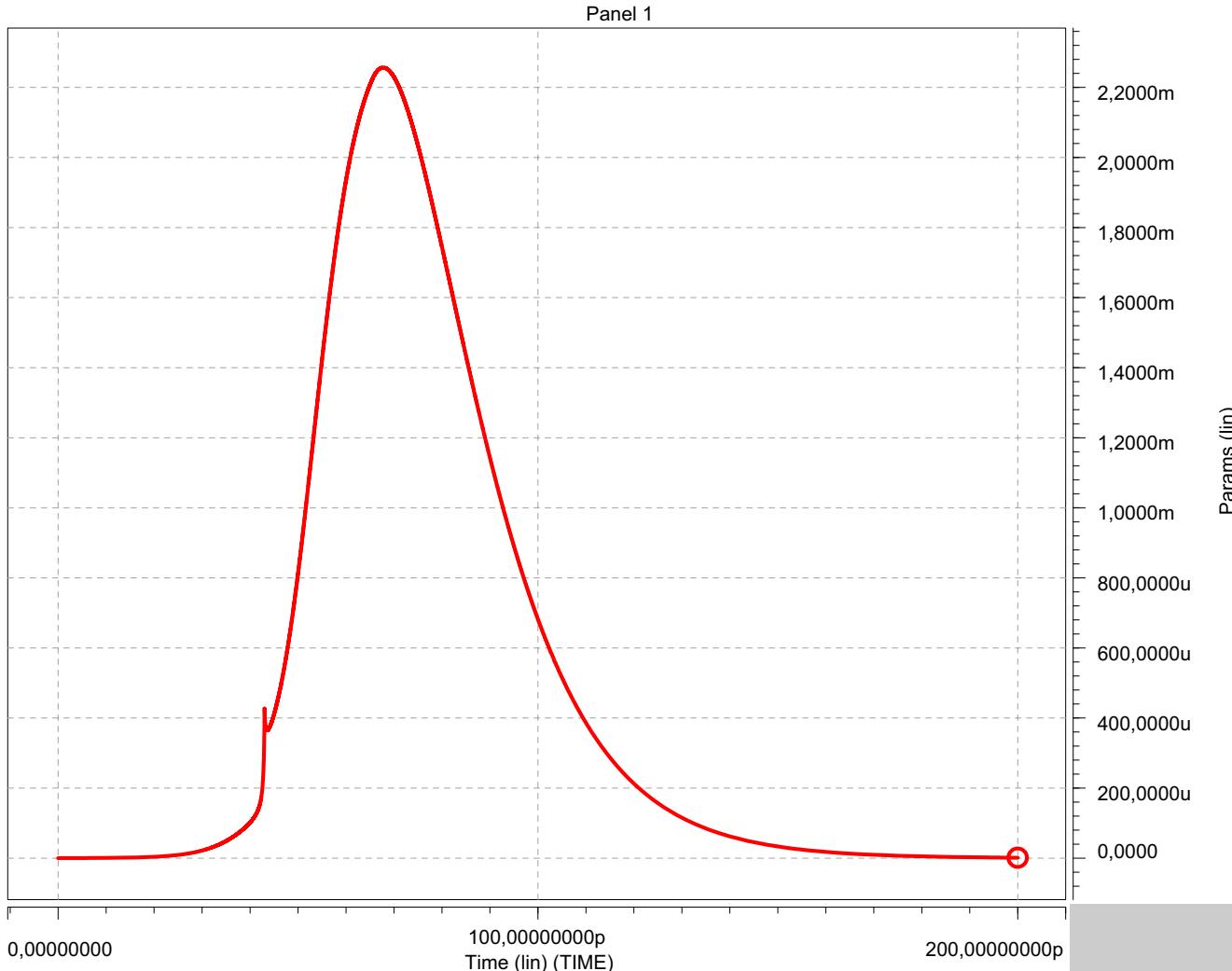
- ◆ Current drawn from  $V_{DD}$  for an 8x8-bit multiplier.

## **CLOSE UP OF ONE CLOCK CYCLE**

- ◆ In a larger circuit, containing many gates, the instantaneous current varies greatly with time.
- ◆ A large and diverse set of test vectors cause transitions to happen in a distributed fashion, over time and space.

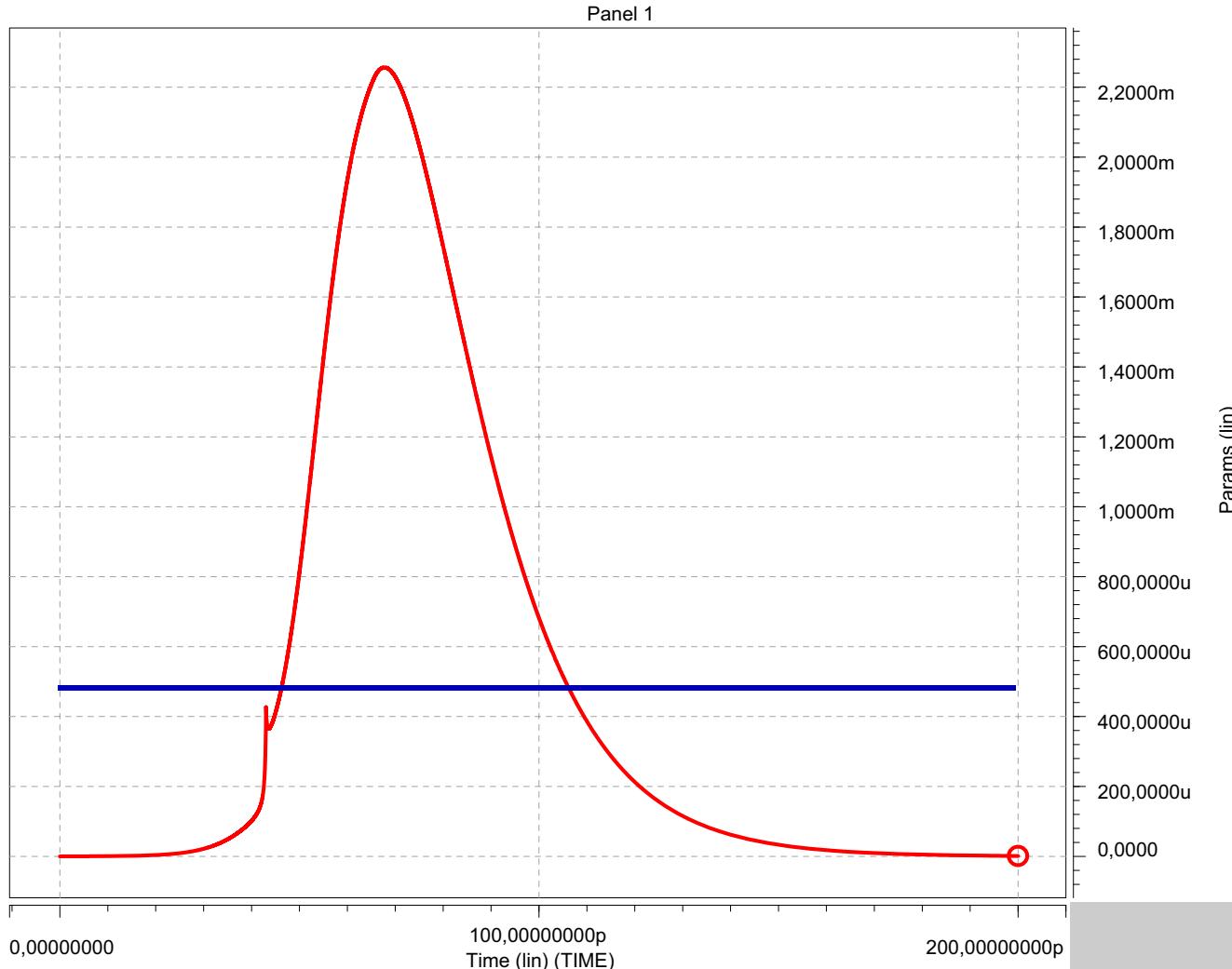


# CHARGING AN INVERTER OUTPUT



$$Q = \int I \, dt$$

# THE AVERAGE CURRENT - THE BLUE LINE



$$I_{\text{avg}} = \frac{\int I \, dt}{T}$$

# ENERGY AND AVERAGE POWER 1(2)

Charge  $Q = I_{\text{avg}} \cdot T$  drawn  
from  $V_{DD}$  to output node



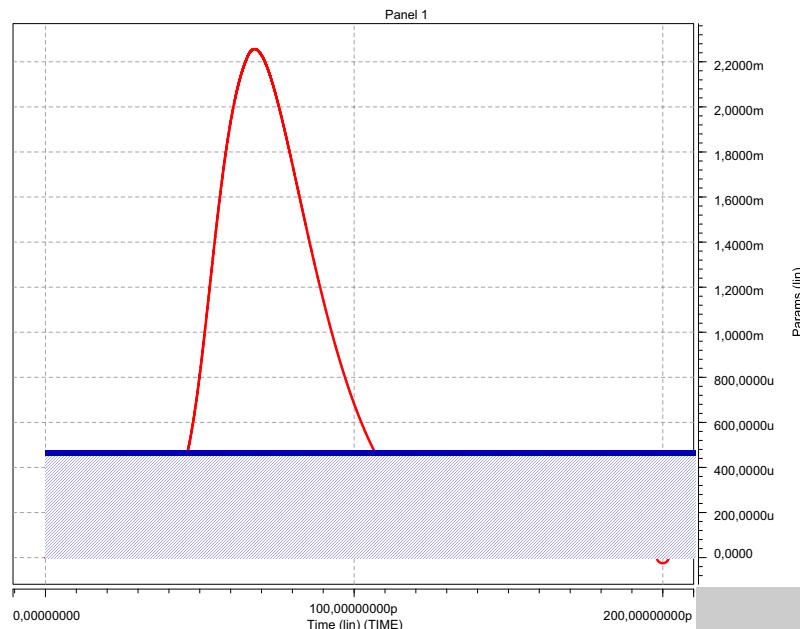
electric energy  $E = Q \cdot V_{DD}$   
extracted from  $V_{DD}$



an average power of

$$P = \frac{Q \cdot V_{DD}}{T} = I_{\text{avg}} \cdot V_{DD}$$

for the clock cycle.



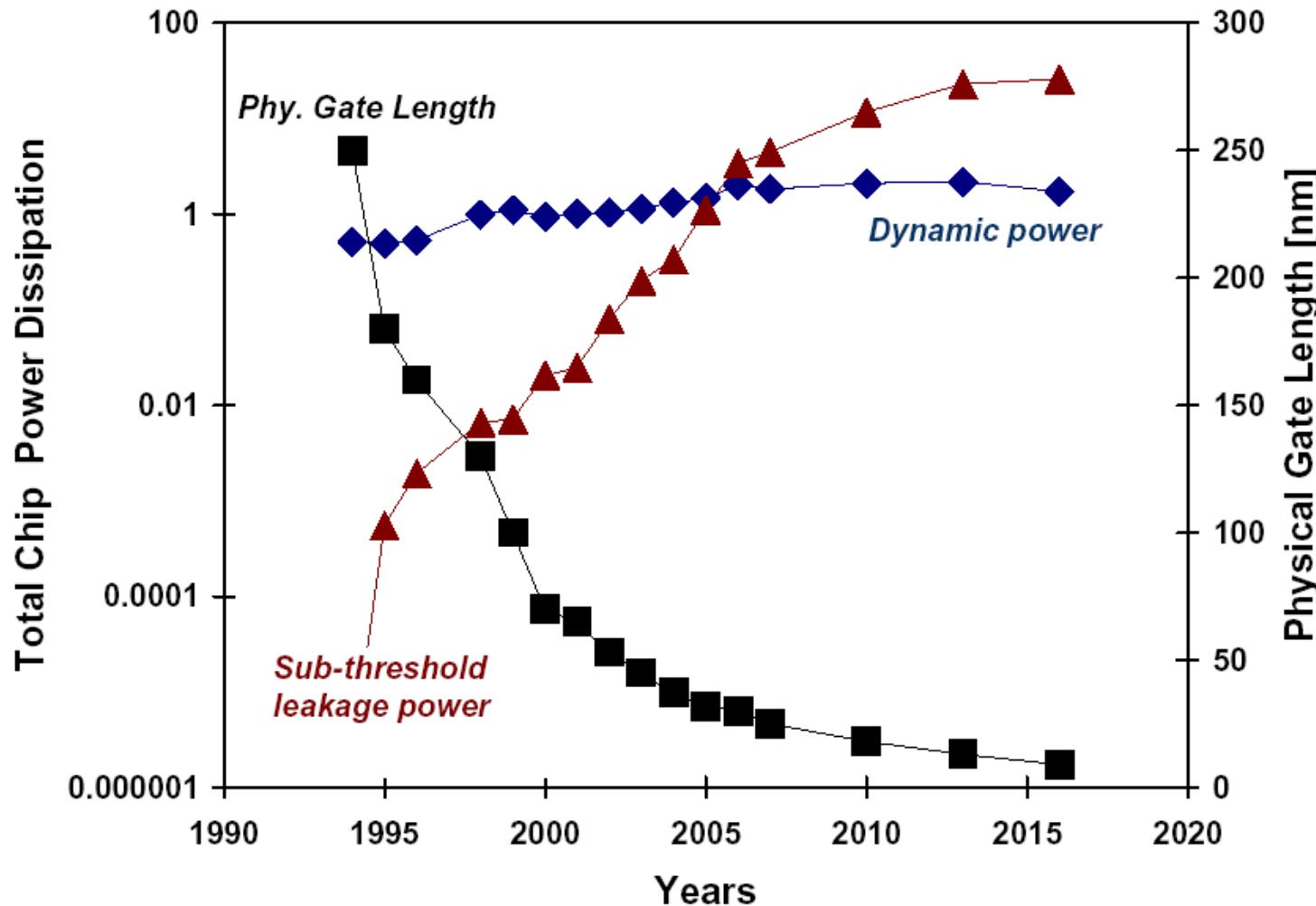
## **ENERGY AND AVERAGE POWER 2(2)**

- ◆ An adder draws an average of 1 mA of current at a supply of 1 V; thus, its power dissipation is 1 mW.
- ◆ The adder energy that is expended for an application is  
$$\text{Energy} = 1 \text{ mW} \cdot \text{Execution time.}$$
- ◆ If the adder performs 1024 one-cycle additions for the application, the total execution time is  
$$\text{Execution time} = 1024 \cdot \text{Clock period.}$$
- ◆ Energy tradeoffs are complex; for example, an increasing circuit complexity (and power dissipation) can lead to faster execution and thus less total energy.

# **DIFFERENT MECHANISMS OF POWER DISSIPATION**

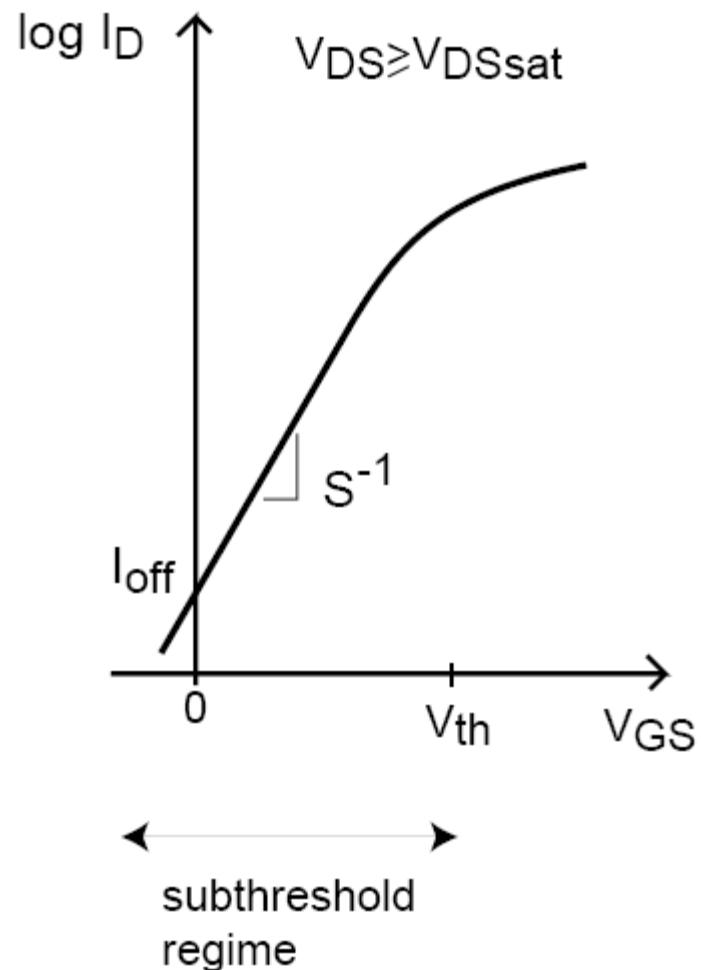
- ◆ Dynamic power dissipation,  $P_{dynamic}$ .
  - Charging/discharging = switching power ( $P_{SW}$ ).
  - (Short-circuit power, negligible in low  $V_{DD}$  processes).
- ◆ Static power dissipation,  $P_{static}$ .
  - Subthreshold leakage power ( $P_{sub}$ ).
  - Gate oxide tunneling leakage.
  - Junction leakage.
- ◆ The dominant portion has been, still is, and should be, switching power.

# ... BUT STATIC POWER HAS BEEN INCREASING



## QUEST FOR Low OFF CURRENTS

- ◆ Subthreshold swing (or subthreshold slope factor,  $S$  below):  
Which change in  $V_{GS}$  results in 10X less current ?



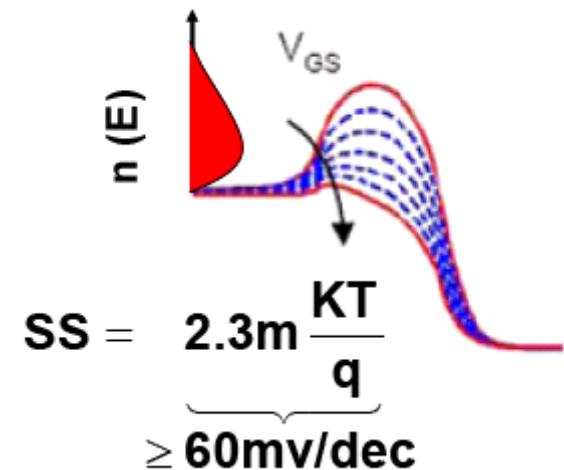
- ◆ The MOSFET's swing is limited to  $>60$  mV/dec (in practice  $>70$  mV/dec).
- ◆ Research on new devices with steeper subthreshold slope is ongoing.

# MOSFET CURRENT IN THE SUBTHRESHOLD REGIME

$$I_{sub} \propto e^{\frac{q(V_{GS} - V_T)}{kT}} \left( 1 - e^{-\frac{qV_{DS}}{kT}} \right), \text{ for } V_{GS} < V_T$$

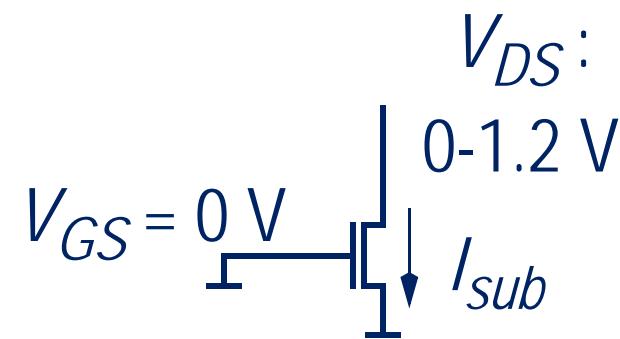
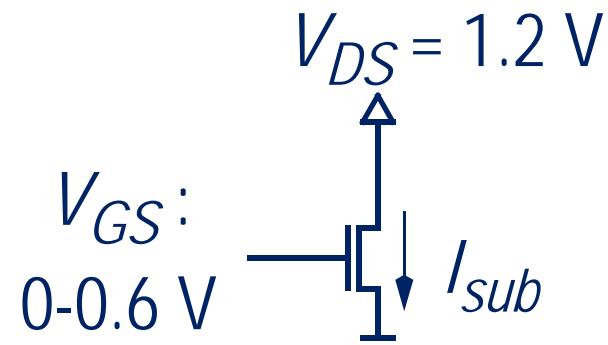
$$V_{thermal} = \frac{kT}{q} = 26 \text{ mV (room temp)}$$

$$\ln(10) \approx 2.3$$



Source: "Band-to-Band Tunneling Field Effect Transistor for Low Power Logic and Memory Applications", S. A. Mookerjea, PhD Thesis, Penn State Univ, 2010.

# CONSIDER SIMULATION OF SINGLE NMOSFET

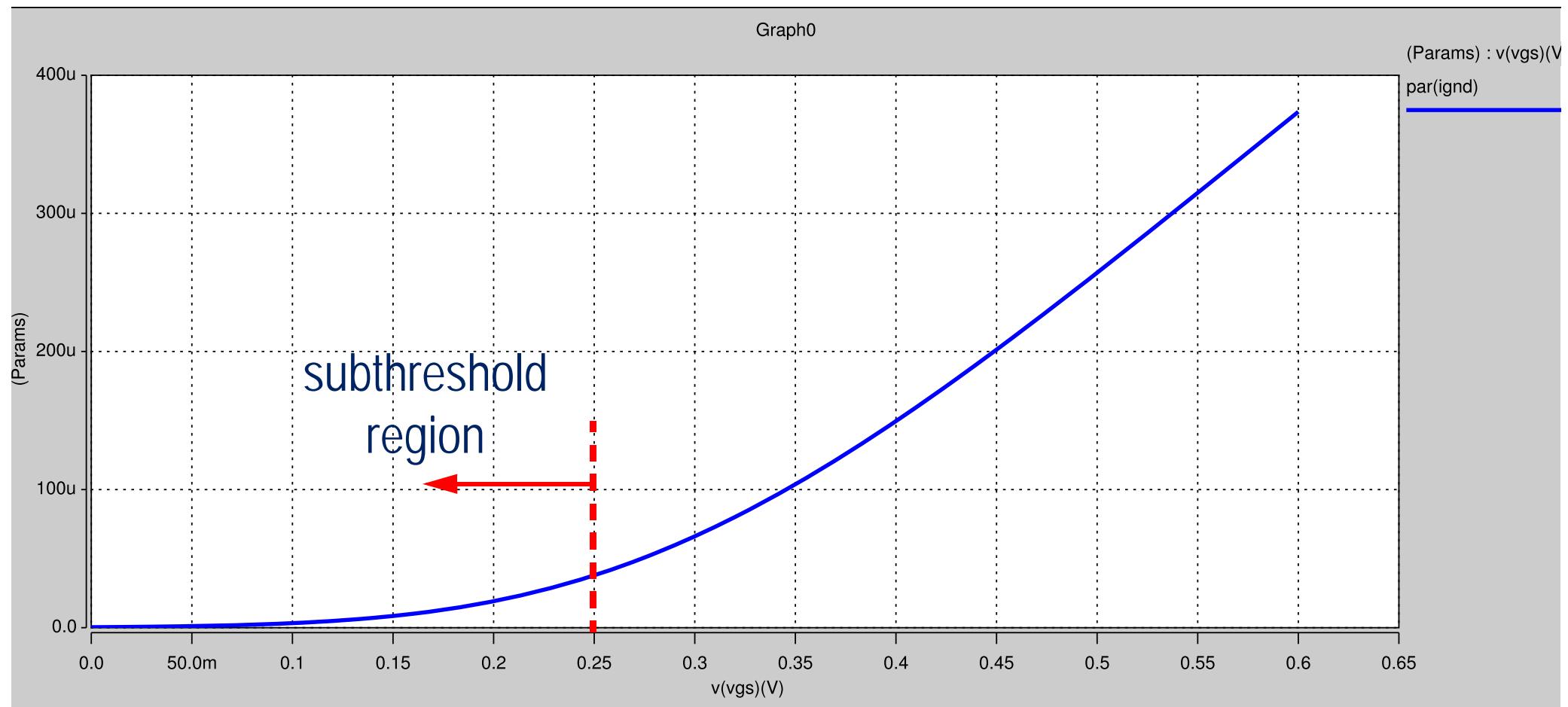


$$I_{sub} \propto e^{\frac{q(V_{GS} - V_T)}{kT}}$$

$$I_{sub} \propto e^{\frac{q(-V_T)}{kT}} \left( 1 - e^{-\frac{qV_{DS}}{kT}} \right)$$

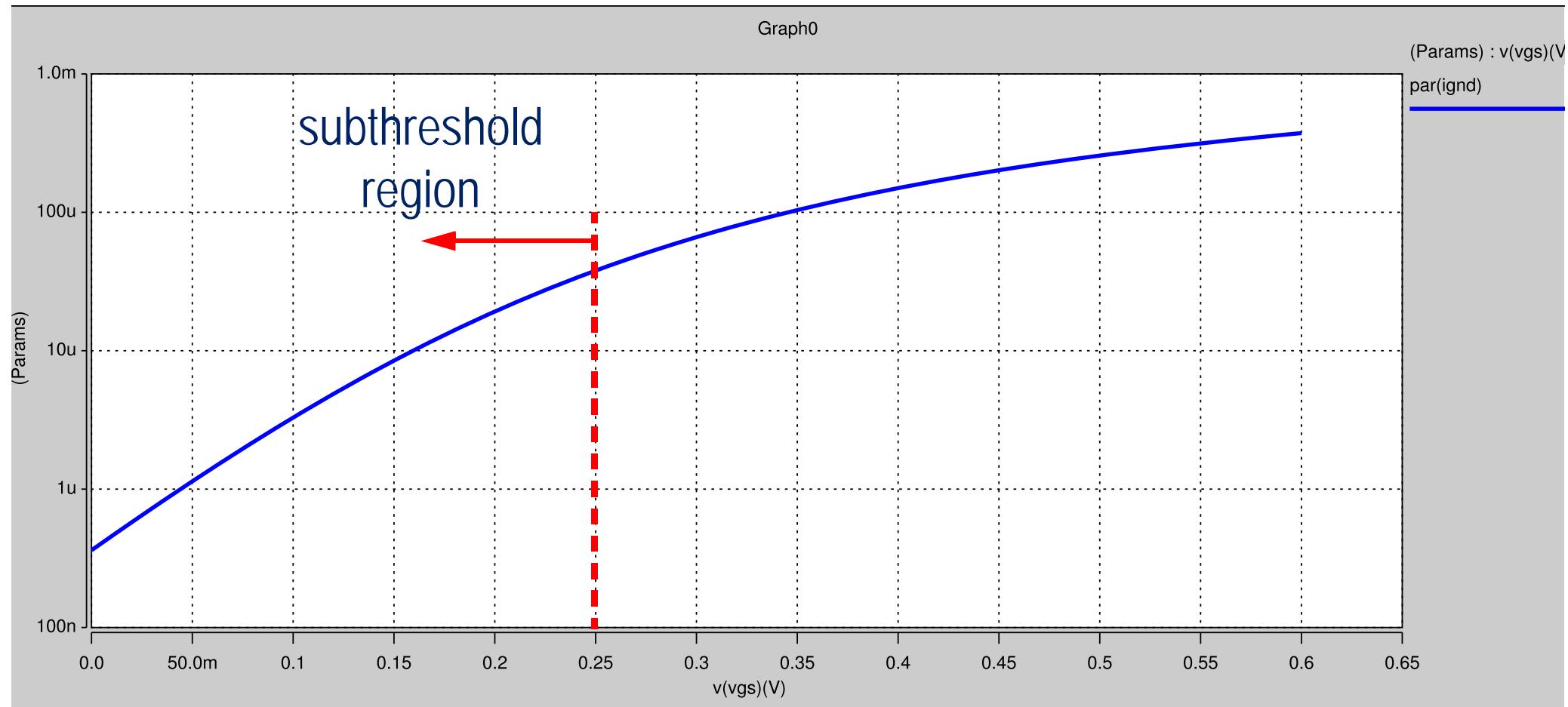
## I<sub>SUB</sub> (LIN) vs V<sub>GS</sub>

- ◆ Simulation of 65nm NMOSFET with  $V_{DS} = 1.2$  V and  $V_T = 0.25$  V:

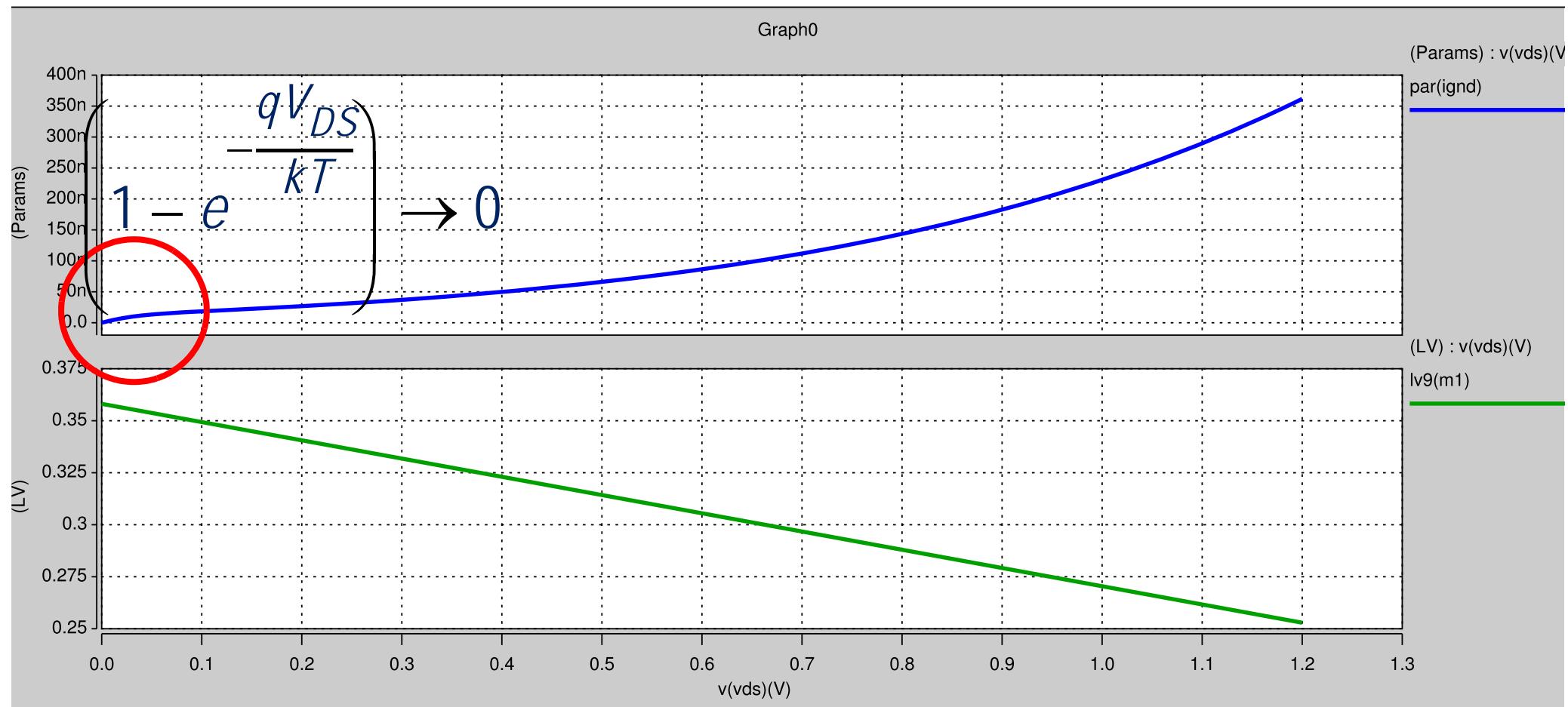


## ISUB (LOG) VS VGS

- ◆ Simulation of 65nm NMOSFET with  $V_{DS} = 1.2$  V and  $V_T = 0.25$  V:



# ISUB VS VDS FOR VGS = 0



$V_T$  varies with  $V_{DS}$ , making  $I_{sub}$  vary with  $V_{DS}$ .

## DIBL 1(2)

$$\blacklozenge \quad I_{sub} \propto e^{\frac{q(V_{GS} - V_T)}{kT}} \left( 1 - e^{-\frac{qV_{DS}}{kT}} \right)$$

which for an offstate NMOSFET ( $V_{GS} = 0$ ,  $V_{DS} = V_{DD}$ ) becomes

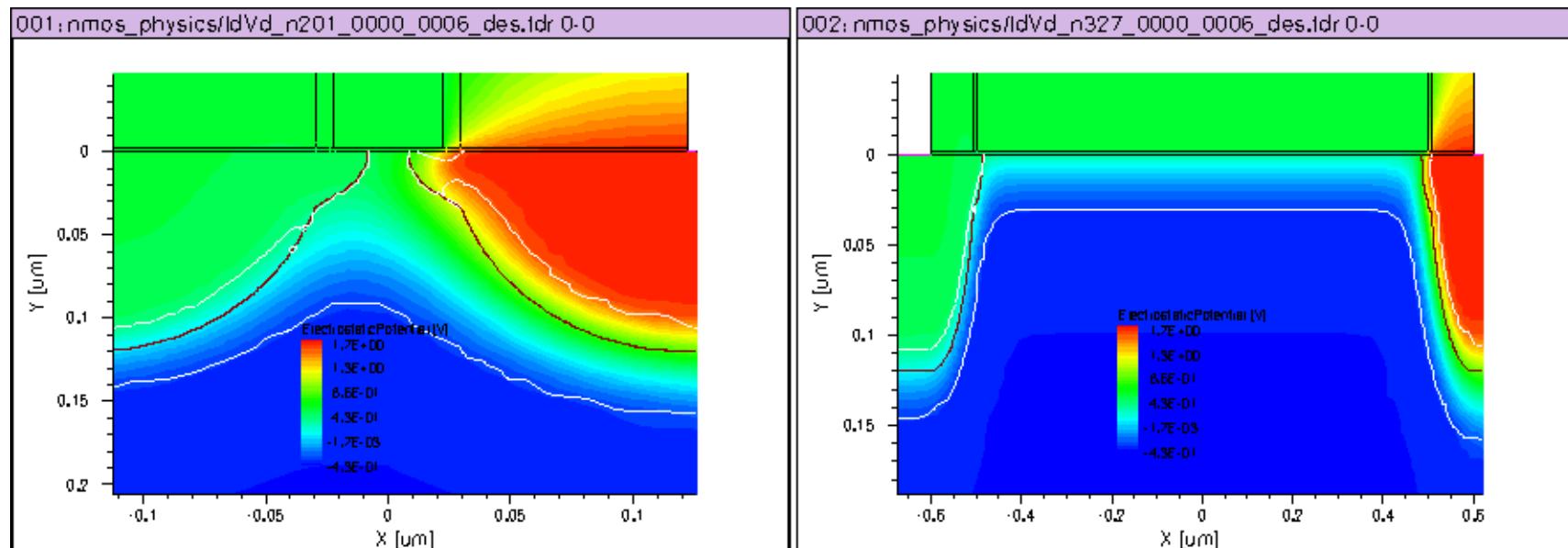
$$I_{sub} \propto e^{-\frac{qV_T}{kT}}$$

where  $V_T$  varies with  $V_{DS}$ . This is because of drain-induced barrier lowering (DIBL) which is a short-channel effect (SCE).

◆ Thus,  $P_{static} = I_{sub} \cdot V_{DD}$  has a strong dependency on  $V_{DD}$ .

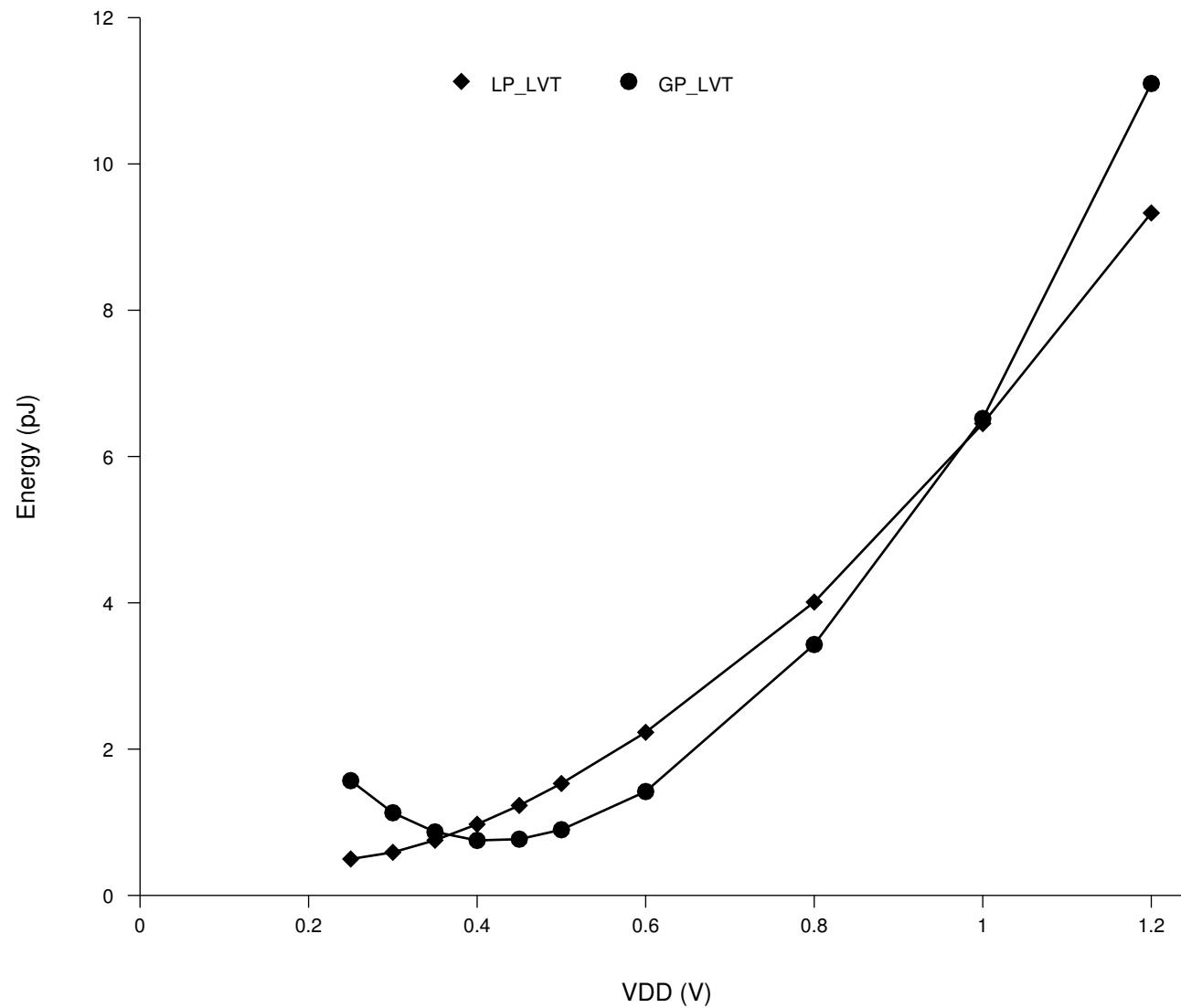
## DIBL 2(2)

- ◆ The drain voltage, which is decided by  $V_{DD}$ , impacts channel electrostatic distribution. A higher  $V_{DD}$  will deplete relatively more of the channel when this is short, which in turn increases  $I_{sub}$ .

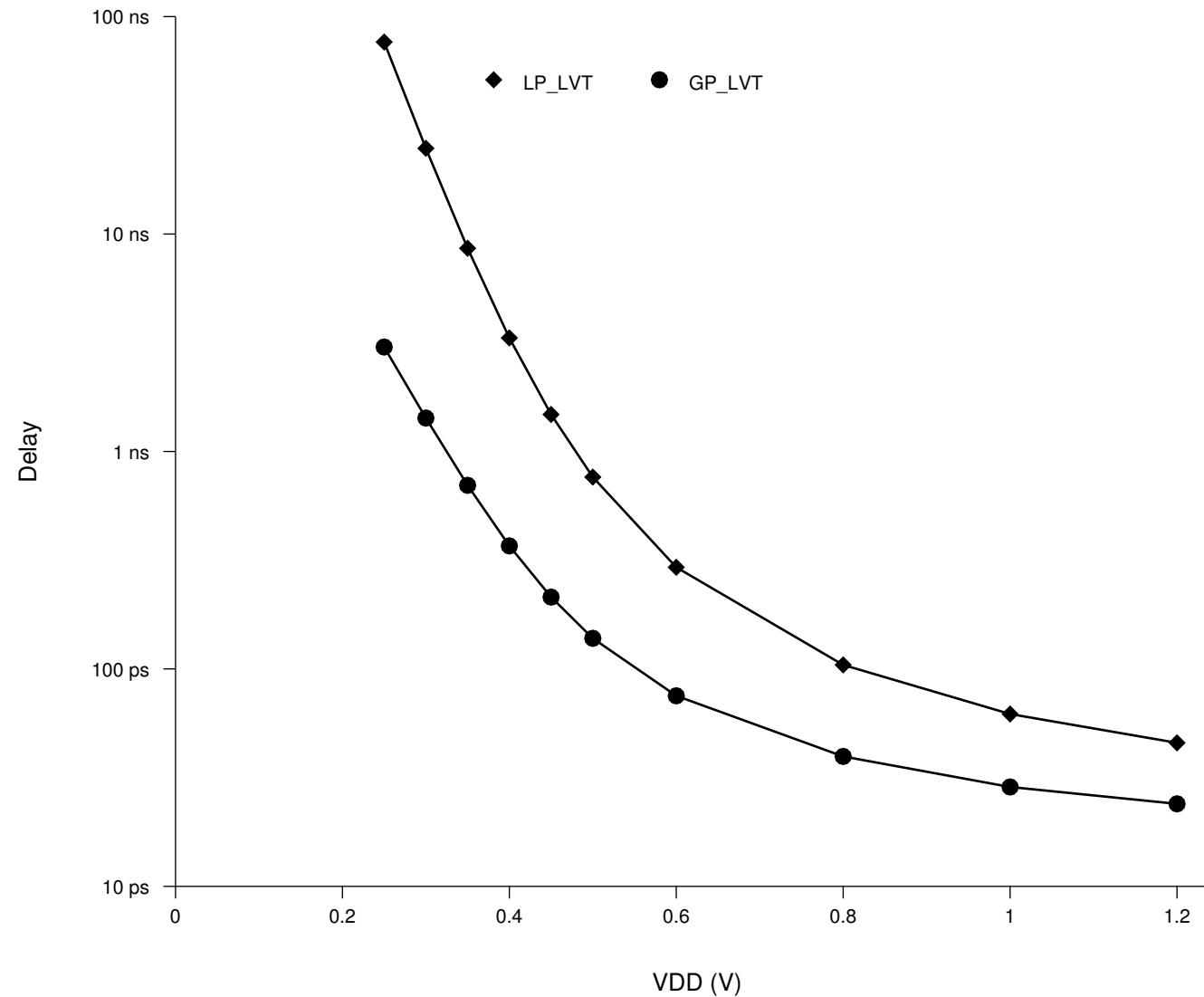


- ◆  $\Delta V_T = -\lambda_d V_{DS}$ , where  $\lambda_d$  is the DIBL coefficient.

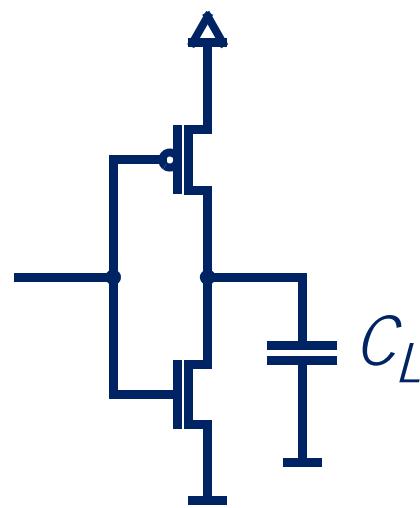
# LOW-VOLTAGE OPERATION IS ENERGY EFFICIENT...



# ...SINCE STATIC POWER DOMINATES SLOW CIRCUITS



# SWITCHING POWER DISSIPATION

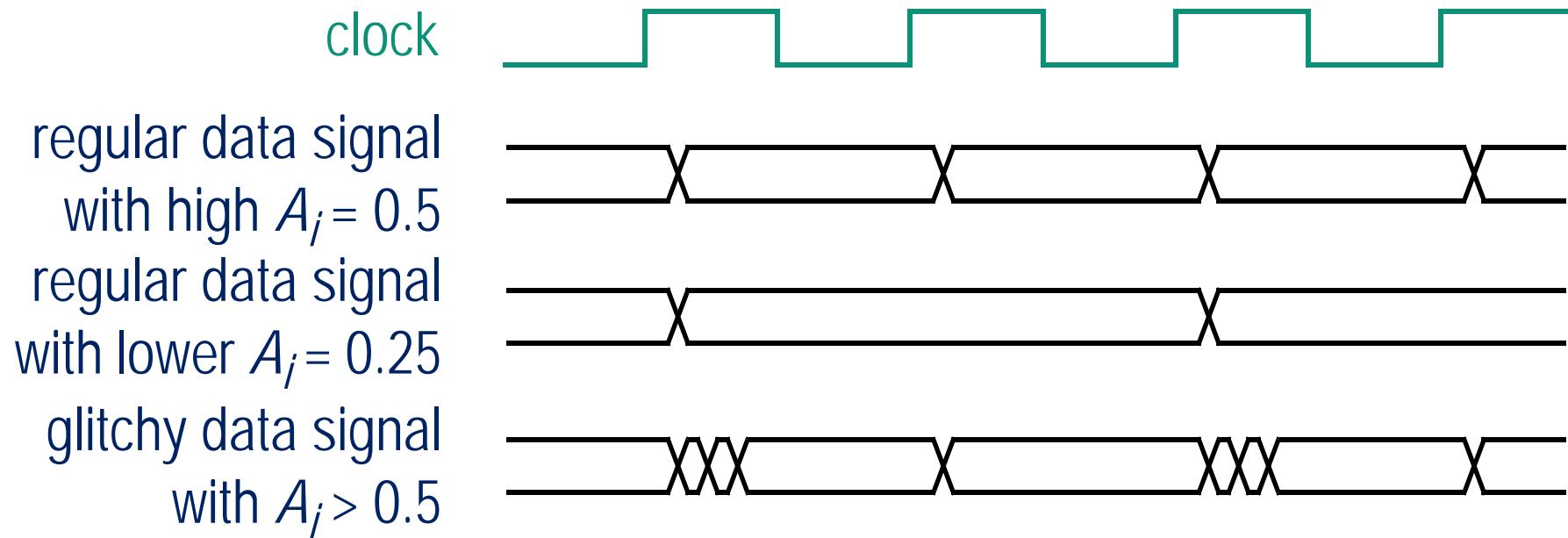


- ◆ It takes energy  $E = Q \cdot V_{DD} = (C_L \cdot V_{DD}) \cdot V_{DD}$  from  $V_{DD}$  to charge the output node.
- ◆ During a full transition (output  $0 \rightarrow 1 \rightarrow 0$ ), the electric energy  $E$  turns into heat.
- ◆ Power dissipation = rate of energy conversion:

$$P_{SW} = \frac{1}{T} \cdot V_{DD}^2 \cdot \text{switched capacitance} = f \cdot V_{DD}^2 \cdot \sum_i A_i \cdot C_i$$

where  $A_i$  is switching activity on node  $i$  (switching activity for  $0 \rightarrow 1$ ).

# SWITCHING ACTIVITY



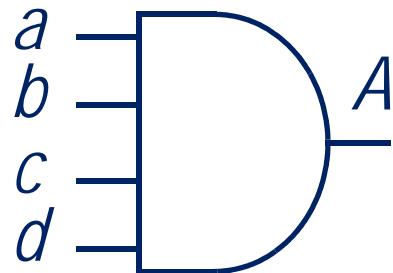
## **SWITCHING ACTIVITY AND PROBABILITY**

- ◆ For a 3-bit truth table,  
the rightmost bit has a switching activity of  $4/8 = 0.5$ ,  
while the leftmost bit has an activity of  $1/8 = 0.125$ .
    - 0.5 is the maximal activity of data signals.
    - 1 is the activity of non-gated clock.
  - ◆ For a 3-bit truth table,  $P(A) = P(B) = P(C) = 0.5$ .  
This means the probability of the bits  
being logical 1s is 0.5.
- |     |
|-----|
| 000 |
| 001 |
| 010 |
| 011 |
| 100 |
| 101 |
| 110 |
| 111 |

## Ex of Simplified Probability Propagation

$P(a:1)$  probability of  $a$  being logical 1.

$P_{0 \rightarrow 1}(a)$  probability of  $a$  switching from 0 to 1.



$$P(a:1) = 0.2 \Rightarrow P_{0 \rightarrow 1}(a) = 0.16.$$

$$P(b:1) = 0.9 \Rightarrow P_{0 \rightarrow 1}(b) = 0.09.$$

$$P(c:1) = 0.7 \Rightarrow P_{0 \rightarrow 1}(c) = 0.21.$$

$$P(d:1) = 0.5 \Rightarrow P_{0 \rightarrow 1}(d) = 0.25.$$

$$P(A:1) = 0.2 \cdot 0.9 \cdot 0.7 \cdot 0.5 = 0.063 \Rightarrow$$

$$P_{0 \rightarrow 1}(A) = (1 - 0.063) \cdot 0.063 \approx \underline{0.059}.$$

## **SWITCHING POWER ANALYSIS 1(2)**

- ◆ Simulation-based (dynamic and iterative) techniques.
  - Simulate the circuit and capture current/power.
  - Choose input vectors - few but representative?
  - What models, what simulator to be used?
- ◆ Probabilistic (static and deterministic) techniques.
  - Propagate signal switching activities at primary inputs, to find switching probabilities of all internal nodes of the circuit.
  - How are primary activities obtained - just guesses or use cases?
  - Correlations (temporal and spatial) are hard to capture.

Read [3.2.4/3.1.4 Logic-Level Power Estimation in Vol 2/Ch 3].

## **SWITCHING POWER ANALYSIS 2(2)**

- ◆ In the lab exercises you will get a chance to work with, first, a probabilistic technique for approximative analyses.
- ◆ Then, for higher accuracy, simulation-based techniques can be employed:
  1. logic simulation is used to establish actual switching activities for a particular set of test vectors (VCD/SAIF), by toggle counting.
  2. the switching activities obtained from simulation are fed to a gate-level power analysis tool that considers both switching and leakage power.

## **WORKING WITH SWITCHING INFORMATION 1(3)**

- ◆ As a result of a simulation, consider a TCF (toggle count format) file:

```
"Clk" : "0.50000 855432000" ;
```

The clock is logic 1 for half of the simulation time.

The second number gives  $855,432,000 / 1e+9 = 0.855$  toggle / ns =  
2 toggles / actual clock period (here 2.338 ns).

- ◆ VCD captures the waveform, while SAIF accumulates toggling count only, to save space:

- SAIF = 572 kB
  - VCD = 7.907 MB.

## **WORKING WITH SWITCHING INFORMATION 2(3)**

- ◆ 1,000 random vectors vs. 233,450 use-case vectors.

- ◆ TCF information for random:

```
"A[15]" : "0.51520 225271000" ;  
"A[16]" : "0.50570 220151000" ;
```

- ◆ TCF information for use case:

```
"A[15]" : "0.04130 29906000" ;  
"A[16]" : "0.54440 143117000" ;
```

## **WORKING WITH SWITCHING INFORMATION 3(3)**

### ◆ TCF information for random:

- $225,271,000 / 1e+9 = 0.222527 \text{ toggle/ns} = 0.5203 \text{ toggles / clock period}$
- $220,151,000 / 1e+9 = 0.220151 \text{ toggle/ns} = 0.5147 \text{ toggles / clock period}$

### ◆ TCF information for use case:

- $29,906,000 / 1e+9 = 0.0699 \text{ toggles / actual clock period}$
- $143,117,000 / 1e+9 = 0.3346 \text{ toggles / actual clock period}$

## THE PARAMETER CALLED TOGG (RC)

- ◆ *togg* (toggling rate) describes how many times a signal toggles during 1 ns. Thus, *togg* fuses information on  $f$  and  $A_i$  as defined in  $P_{SW}$ : 
$$f \cdot V_{DD}^2 \cdot \sum_i A_i \cdot C_i$$
  - *togg*=1 could either mean that you have a signal with  $f = 500$  MHz and  $A_i = 1$ , or  $f = 1$  GHz and  $A_i = 0.5$ , or ...
  - $A_i$  only counts  $0 \rightarrow 1$  transitions, while *togg* counts both  $0 \rightarrow 1$  and  $1 \rightarrow 0$ .
- ◆ *togg* = ' $f$  normalized to 1 GHz' \*  $(A_i^2)$ , for example,  $(0.769 \text{ GHz}/1 \text{ GHz}) \cdot (0.2^2) = 0.308$ .

## **USE CASES VERSUS RANDOM DATA**

- ◆ Power report for random data:

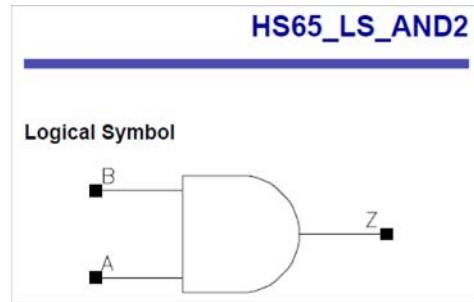
Instance	Cells	Leakage Power (nW)	Dynamic Power (nW)	Total Power (nW)
<hr/>				
ALU	949	314,465	8,791,824	9,106,290

- ◆ Power report for use-case test vectors

Instance	Cells	Leakage Power (nW)	Dynamic Power (nW)	Total Power (nW)
<hr/>				
ALU	949	319,967	4,218,725	4,538,692

- ◆ Power depends strongly on input data.

# CELL-LIBRARY POWER DISSIPATION PROPERTIES



Average Leakage Power (mW) at 25C, 1.20V Typ process

	vdd
X4	1.251e-07
X9	2.207e-07
X18	4.318e-07
X27	6.691e-07
X35	8.865e-07

Internal Energy (uW/MHz) at Minimum Output Load

Pin Cycle (vdd)	X4	X9
A (stable)	5.170e-05	9.591e
B (stable)	1.903e-04	3.556e
A to Z	5.500e-03	8.875e
B to Z	5.203e-03	8.359e

Pin Capacitance (pf) at 25C, 1.20V Typ process

A	0.0010	
B	0.0012	

# **POWER COMPONENTS IN RTL COMPILER**

## ◆ Leakage power dissipation.

- Leakage power annotation in the synthesis library.
- Multi- $V_T$  cells (for example, high  $V_T \Rightarrow$  low leakage power, slow = poor timing performance) are supported in RTL Compiler.

## ◆ Dynamic power dissipation.

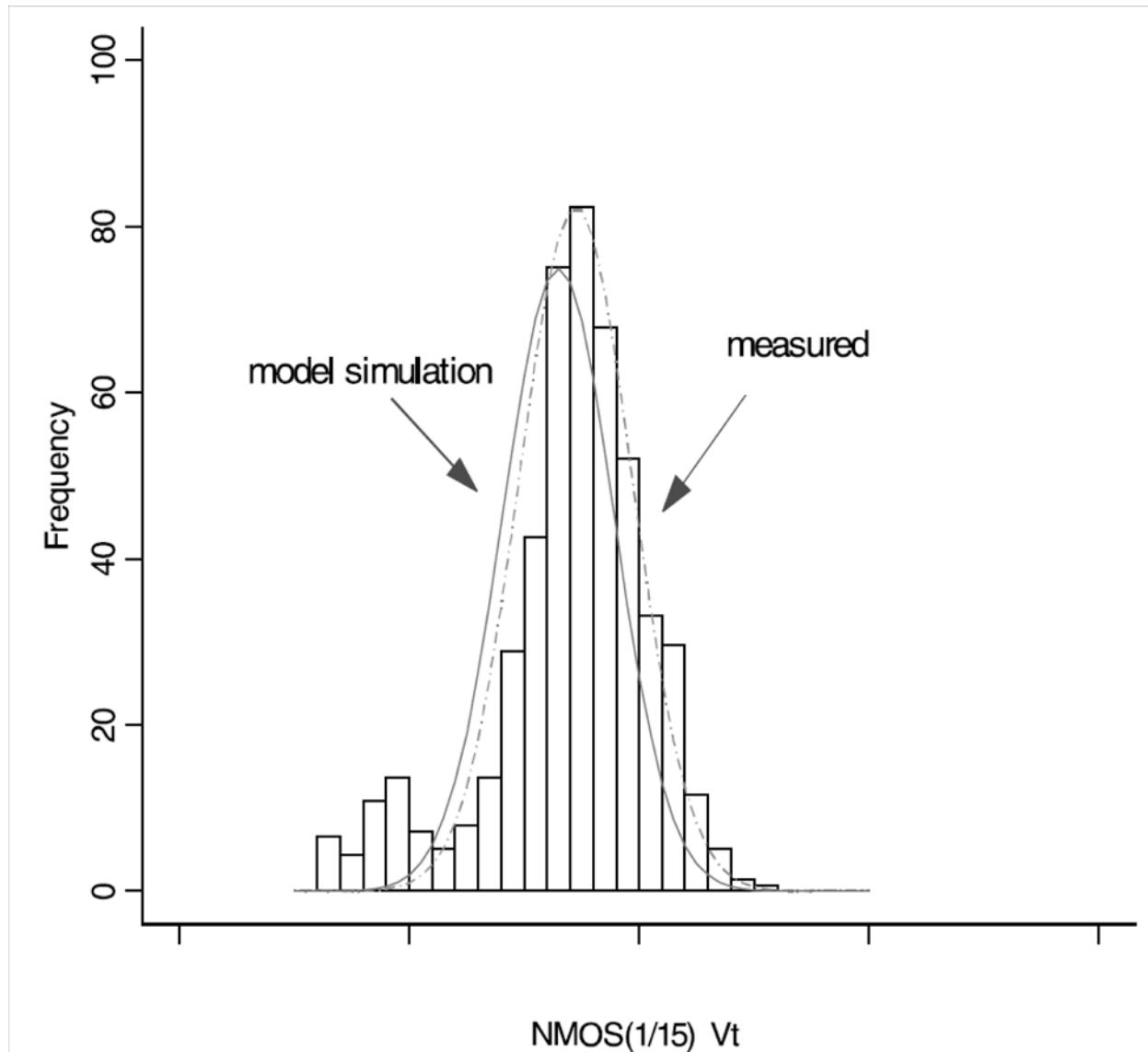
- Includes switching and short-circuit power.
- Both internal to cell and wires between cells.

## EVALUATING POWER AND ENERGY

- ◆ To get low power dissipation,  
simply reduce clock rate; **UNFAIR!**
- ◆ When comparing circuits, use a reasonable metric:
  - First, ensure the circuit fulfils the performance requirement.
  - Use power-delay-product (*this gives energy per clock cycle*).
  - Or use energy-delay-product.

# Variability

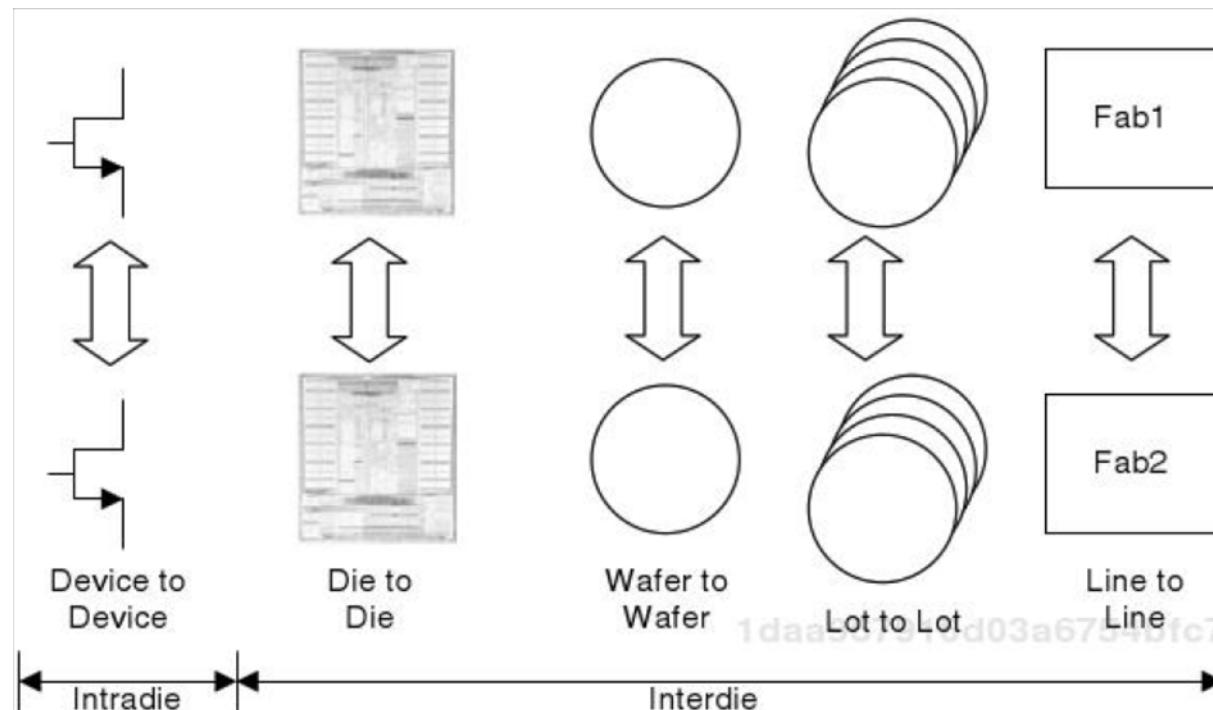
# DEVICE PARAMETERS VARY



Source: Qiang Zhang et al., Solid-State Electronics 2001

# DIFFERENT TYPES OF VARIATION

- ◆ Variations manifest in different ways.
  - Between dies on the same wafer - inter-die variations.
  - Between cells/blocks on the same die - intra-die variations.

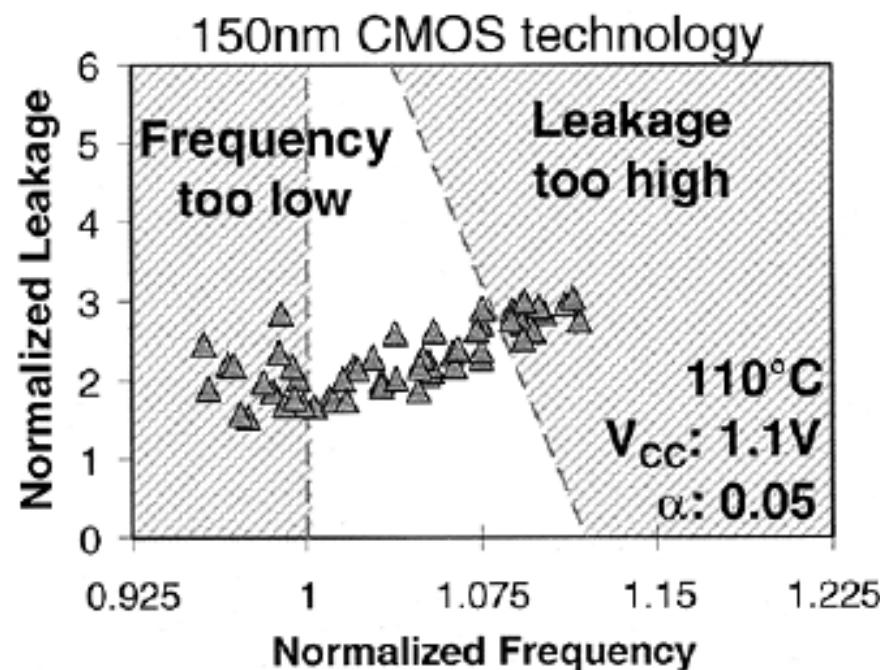


Source: Wang et al.,  
Nano-CMOS Circuit and  
Physical Design, 2005

# COMBATTING VARIATIONS

- ◆ Static power is a strong function of process and operational parameters. Thus, variations affect power dramatically.
- ◆ Performance and power binning is common to qualify processors.
  - Body biasing can be used at production to fine tune threshold voltages.

$$I_{OFF} \propto e^{\frac{q(V_{GS} - V_T)}{kT}}$$

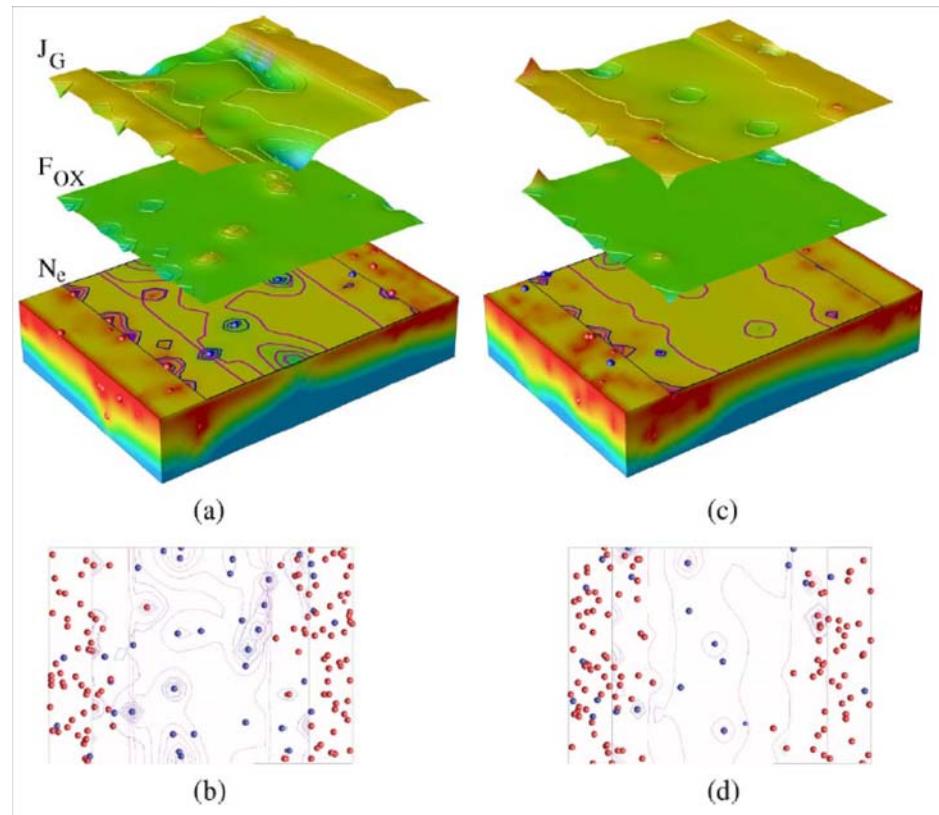


Source: Adaptive Body Bias for Reducing Impacts of Die-to-Die and Within-Die Parameter Variations on Microprocessor Frequency and Leakage, IEEE JSSC, 2002.

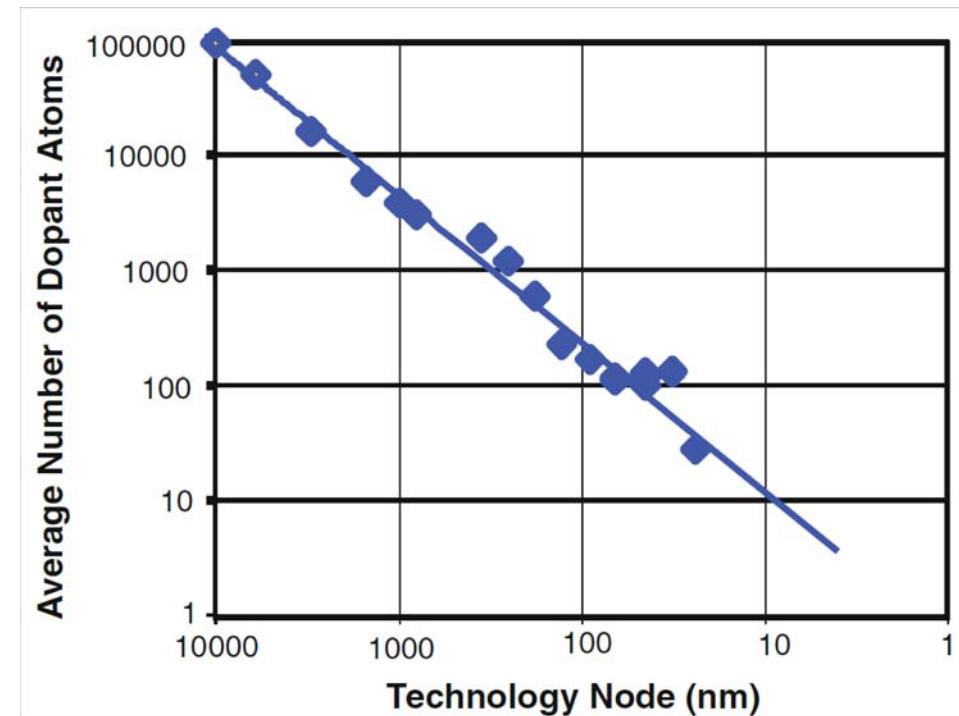
# **SCALING INCREASES PARAMETER VARIATIONS**

- ◆ Static variations.
  - Imperfect manufacturing (CMP, lithography):  
Systematic variations.
  - Small devices means very few dopants:  
Random fluctuations.
- ◆ Dynamic variations.
  - Temperature changes.
  - Different operating modes (power on/off) and different test vectors are used.

# RANDOM DOPANT FLUCTUATION



Source: Direct Tunnelling Gate Leakage Variability  
in Nano-CMOS Transistors, IEEE TED, 2010.

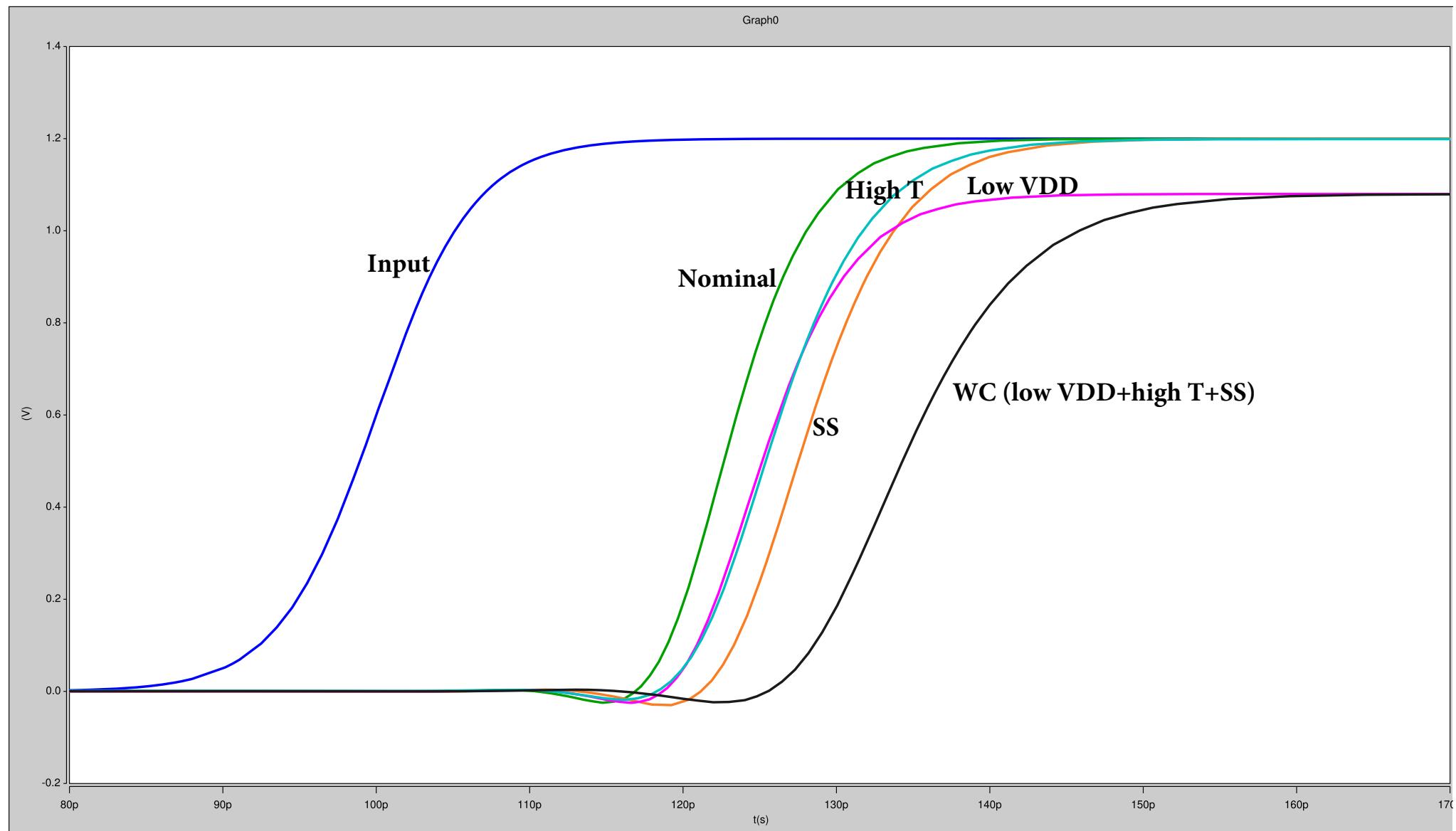


Source: Analog IC Reliability in Nanometer CMOS,  
Springer, 2013.

## **VARIATION-AWARE DESIGN**

- ◆ Given the I-V relation for MOSFETs, vary any of  $tox$  ( $\Rightarrow Cox$ ),  $W$ ,  $L$  or  $VT$  and think about impact on delay.
  - For example, a reduced  $W$  increases delay.
- ◆ Consider variations by using design corners (PVT) or only process corners (P).
- ◆ Use variation-aware simulation strategies.
  - Sigma-based simulation.
  - Monte-Carlo (random) simulation.

# IMPACT OF DESIGN CORNERS ON DELAY

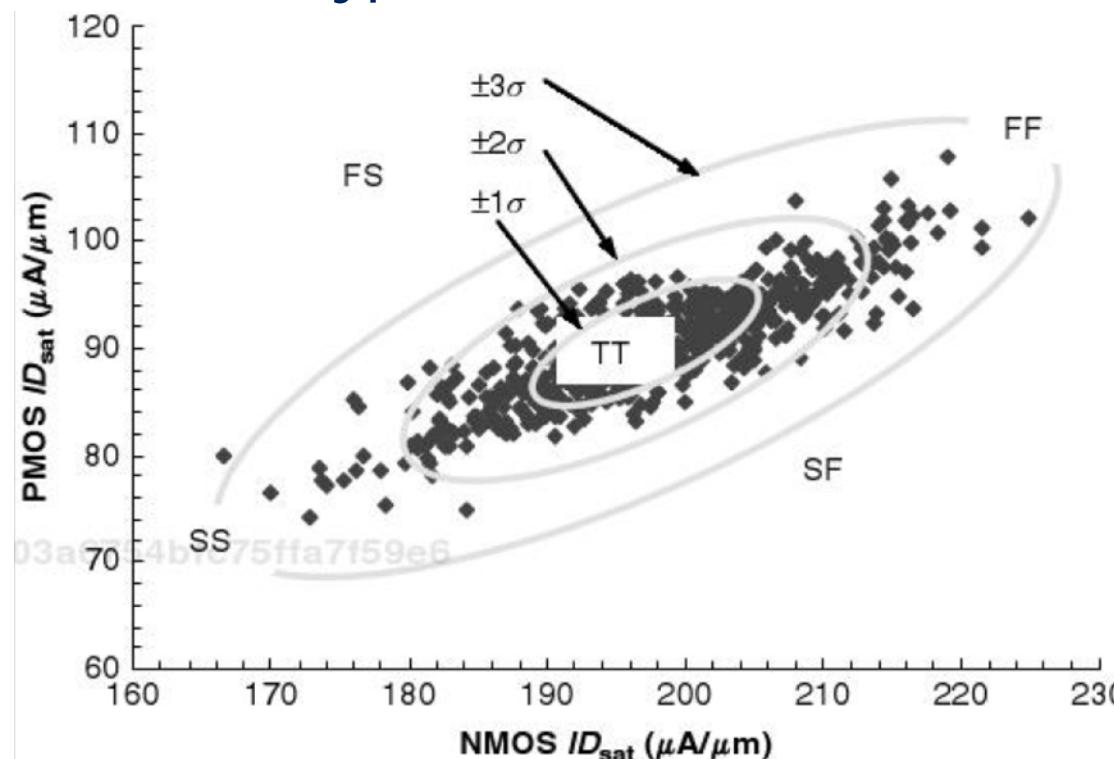


# **PROCESS, VOLTAGE AND TEMPERATURE (PVT)**

- ◆ Static variations (P - process).
  - Process variation captured in process corners.
  - Fast, Typical/Nominal, Slow.
- ◆ Dynamic variations (V - supply voltage, T - temperature).
  - Supply voltage changes with current computation (*IR drop + switching noise are treated later*).
  - Die temperature depends on ambient temperature, cooling system, and on current and past computation pattern.

## PROCESS CORNERS

- ◆ Process corners refer to fabricated transistors turning out to be fast, slow or nominal/typical.
- ◆ FS = Fast NMOS, Slow PMOS, while TT= Typical NMOS, Typical PMOS.

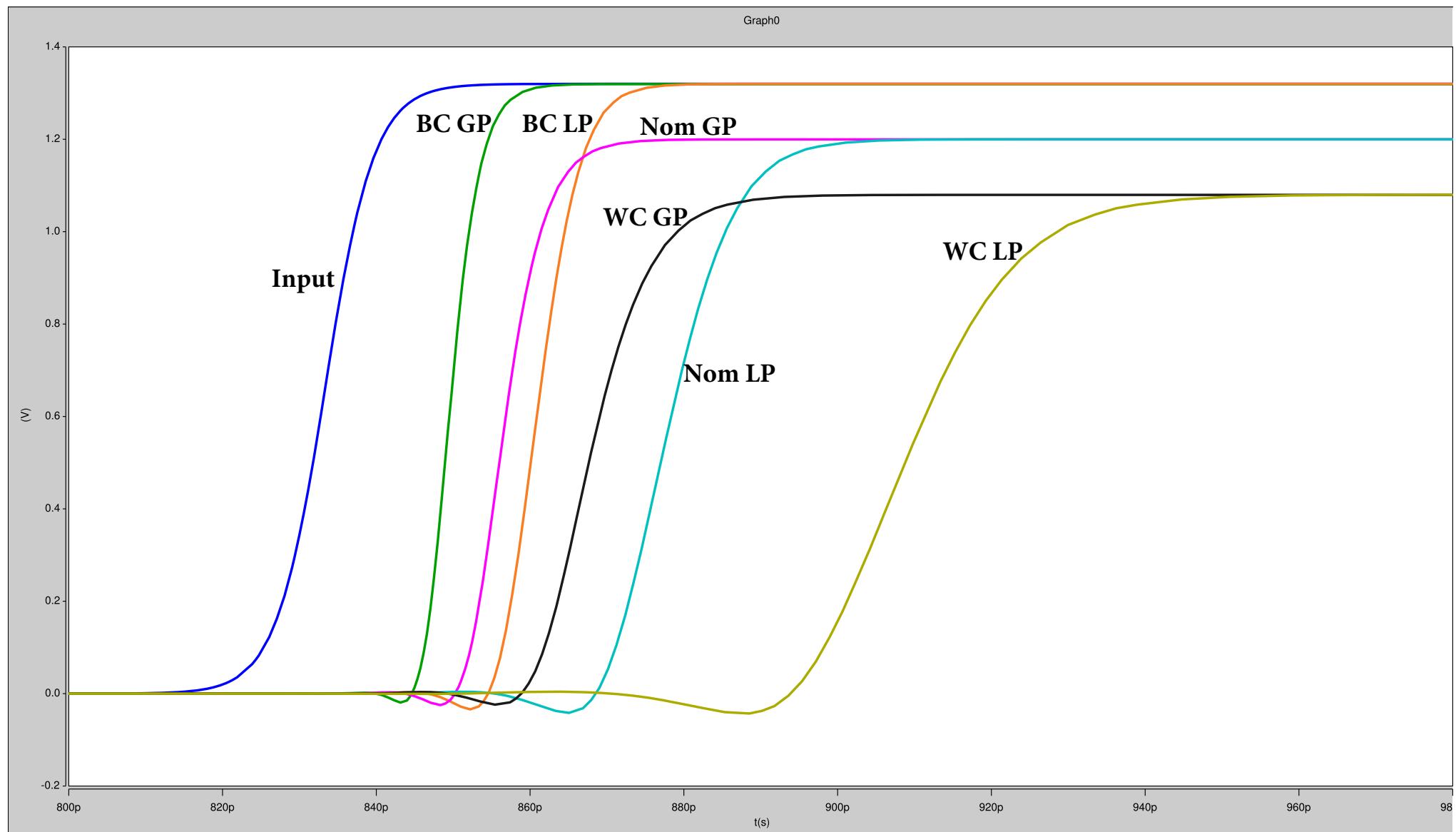


Source: Wang et al.,  
Nano-CMOS Circuit and  
Physical Design, Wiley, 2005

## **CORNER-BASED DESIGN**

- ◆ Important to run setup time analysis for worst-case timing conditions, that is, **Slow NMOS + Slow PMOS + High T + Low VDD.**
- ◆ Conversely it is important to check for hold time violations under best-case timing conditions: **Fast NMOS + Fast PMOS + Low T + High VDD.**
- ◆ Power analysis can be done for typical conditions, while worst-case static power can be analyzed using best-case timing.

# IMPACT OF WORST- AND BEST CASE CONDITIONS



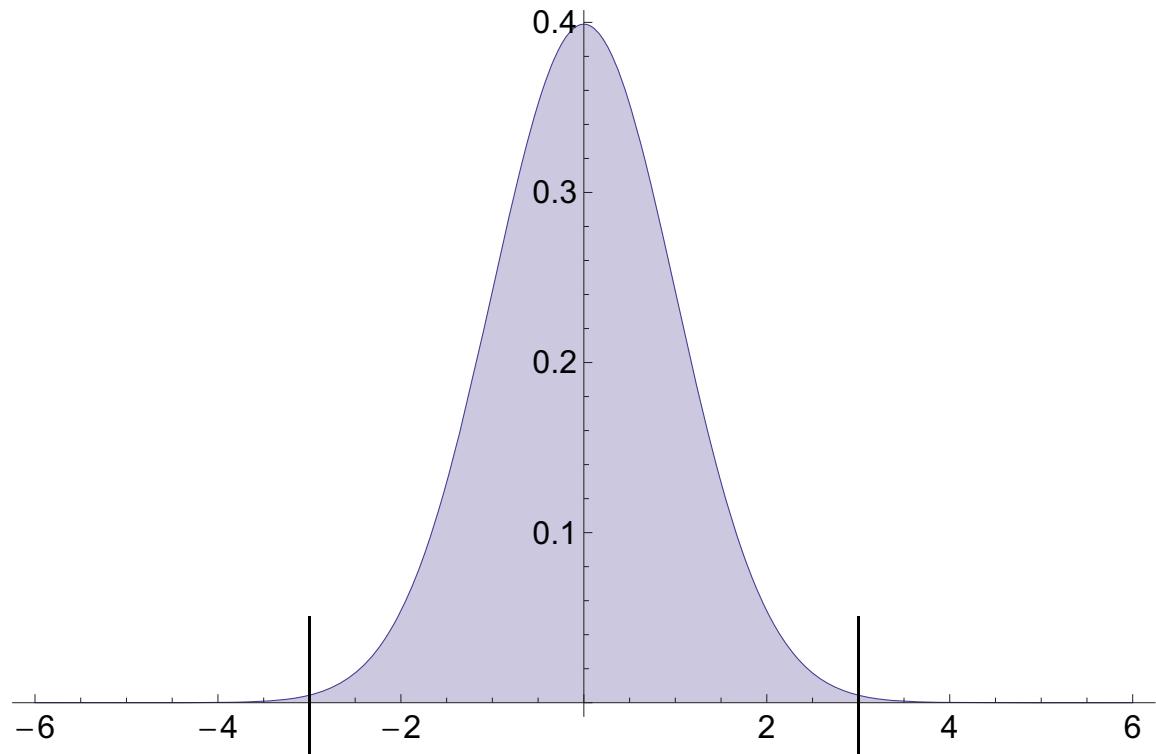
## **METHODS LABS**

- ◆ /usr/local/cad/stm-cmos065-5.4/CORE65LPSVT/5.2.c/libs/  
CORE65LPSVT\_nom\_1.20V\_25C.lib
- ◆ [\[Assignment 3.3.2\]](#): CORE65GPSVT\_nom\_1.10V\_125C.lib
- ◆ mmmc.tcl:

```
# Define delay corners and analysis views.  
create_delay_corner -name typical_corner \  
-library_set typical_lib \  
-rc_corner typical_rc
```

## **STANDARD NORMAL DISTRIBUTION**

- ◆ Random parameters are described with a probability density function (PDF) that follows a normal distribution.
- ◆ The standard deviation is denoted *sigma*,  $\sigma$ .



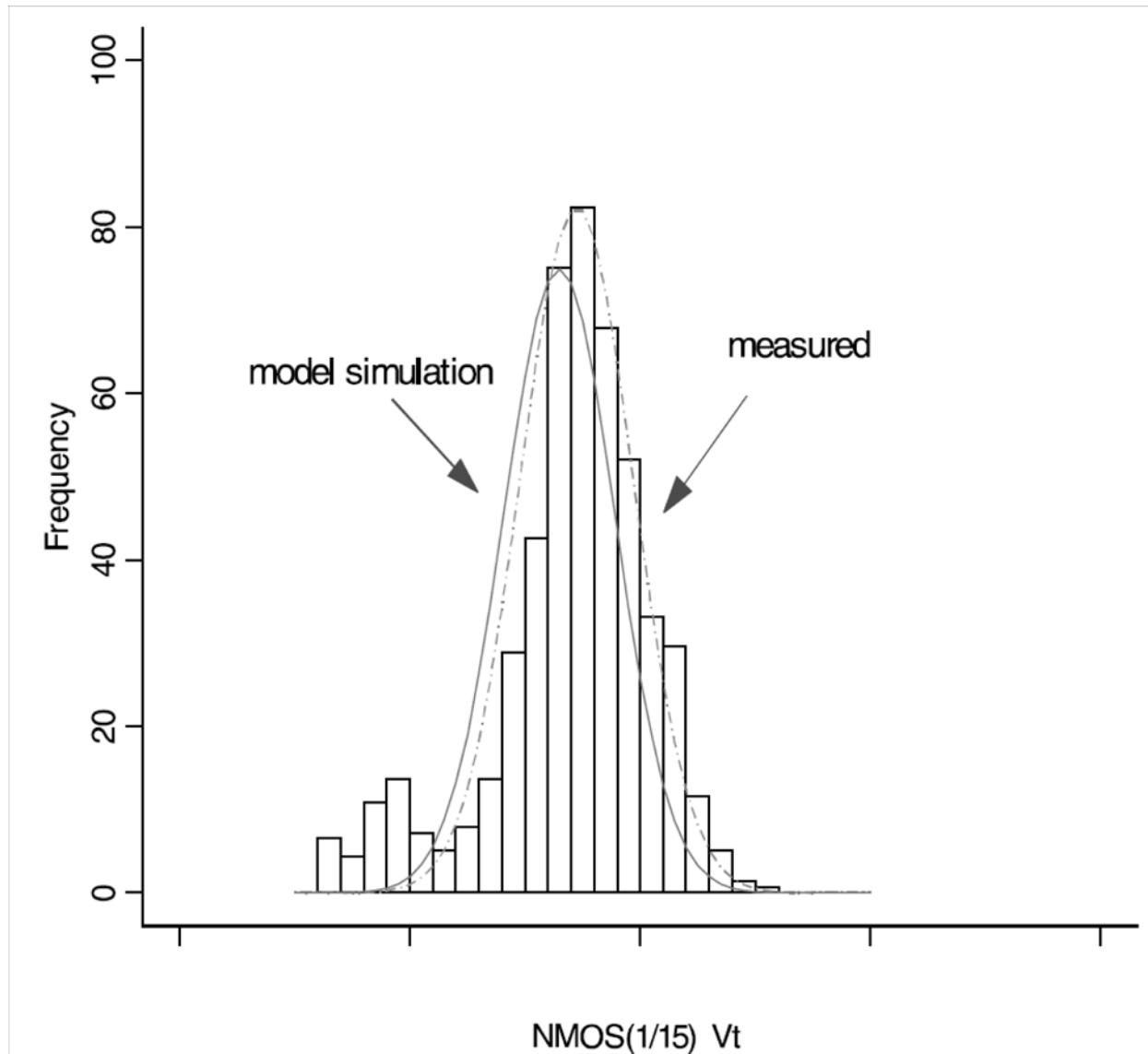
$$\frac{1}{\sqrt{2\pi}\sigma} e^{-\frac{(x-\mu)^2}{2\sigma^2}}$$

*Left graph:*

$\sigma = 1$  and  $\mu = 0$ .

$x \in [-3, 3]$  captures 99.73% of the total area of curve.

# MEASUREMENTS VS MODEL



## APPLYING STATISTICS TO MEASUREMENTS

1. Standard deviation known a priori (experience) as 2 nm.
2. Make 15 measurement samples  $\Rightarrow$  sample mean = 20 nm

3. Assume 95% confidence is sought for  $\Rightarrow$  
$$\int_{-1.96}^{1.96} \frac{1}{\sqrt{2\pi} \cdot \sigma} e^{-\frac{(x-\mu)^2}{2\sigma^2}} dx$$
 since  $x \in [-1.96 \sigma, 1.96 \sigma]$   $\Rightarrow$  95% of standard normal curve area.
4. The true mean is:  $20 \pm 1.96 \frac{2}{\sqrt{15}}$ .

## SOME SIGMA-BASED SIMULATIONS FOLLOW

```
$ Polysilicon Critical Dimensions
+ polycd=agauss(0,0.06u,1) xl='polycd-sigma*0.06u'

$ Active area Critical Dimensions
+ nactcd=agauss(0,0.3u,1) xwn='nactcd+sigma*0.3u'
+ pactcd=agauss(0,0.3u,1) xwp='pactcd+sigma*0.3u'

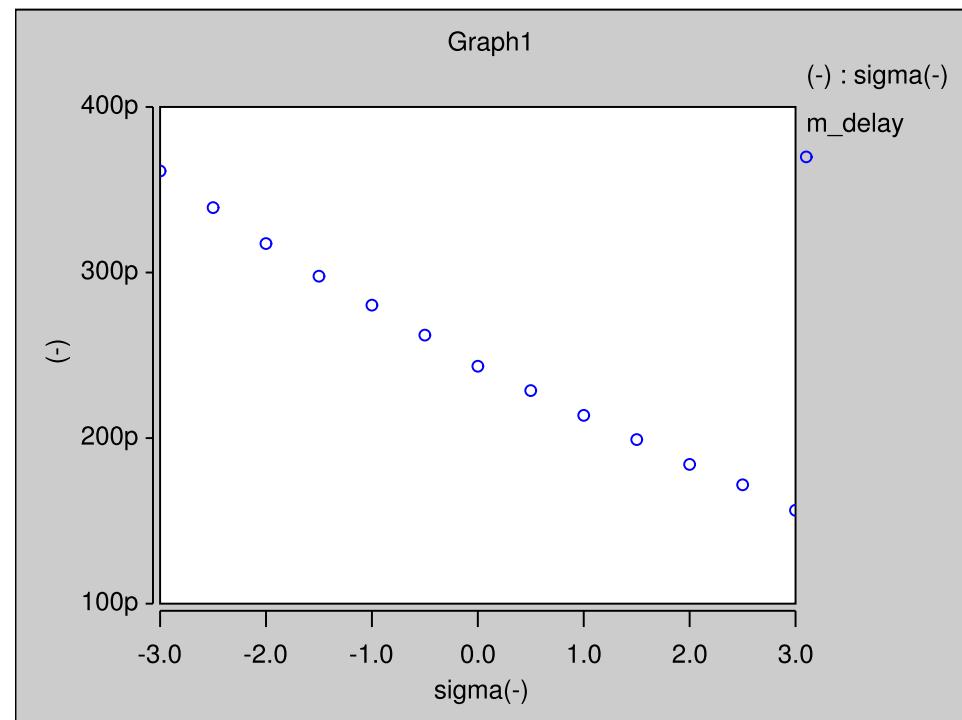
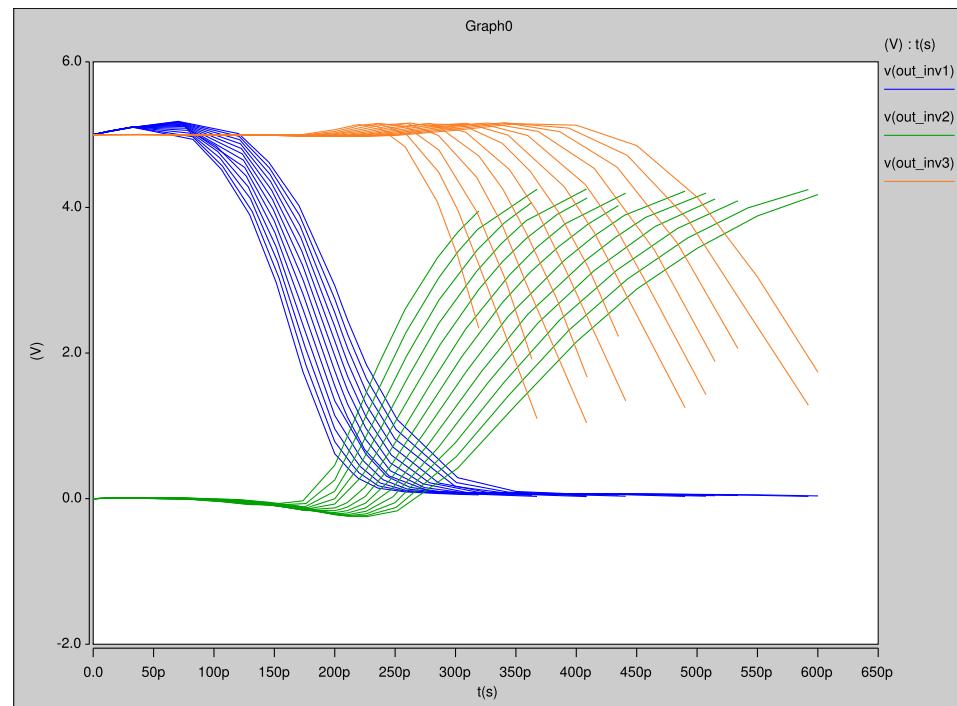
$ Gate Oxide Critical Dimensions
+ toxcd=agauss(200,10,1) tox='toxcd-sigma*10'

$ Threshold voltage variation
+ vtoncd=agauss(0,0.05v,1) delvton='vtoncd-sigma*0.05'
+ vtopcd=agauss(0,0.05v,1) delvtop='vtopcd+sigma*0.05'

$ Active layer resistivity variation
+ rshncd=agauss(50,8,1) rshn='rshncd-sigma*8'
+ rshpcd=agauss(150,20,1) rshtp='rshpcd-sigma*20'
```

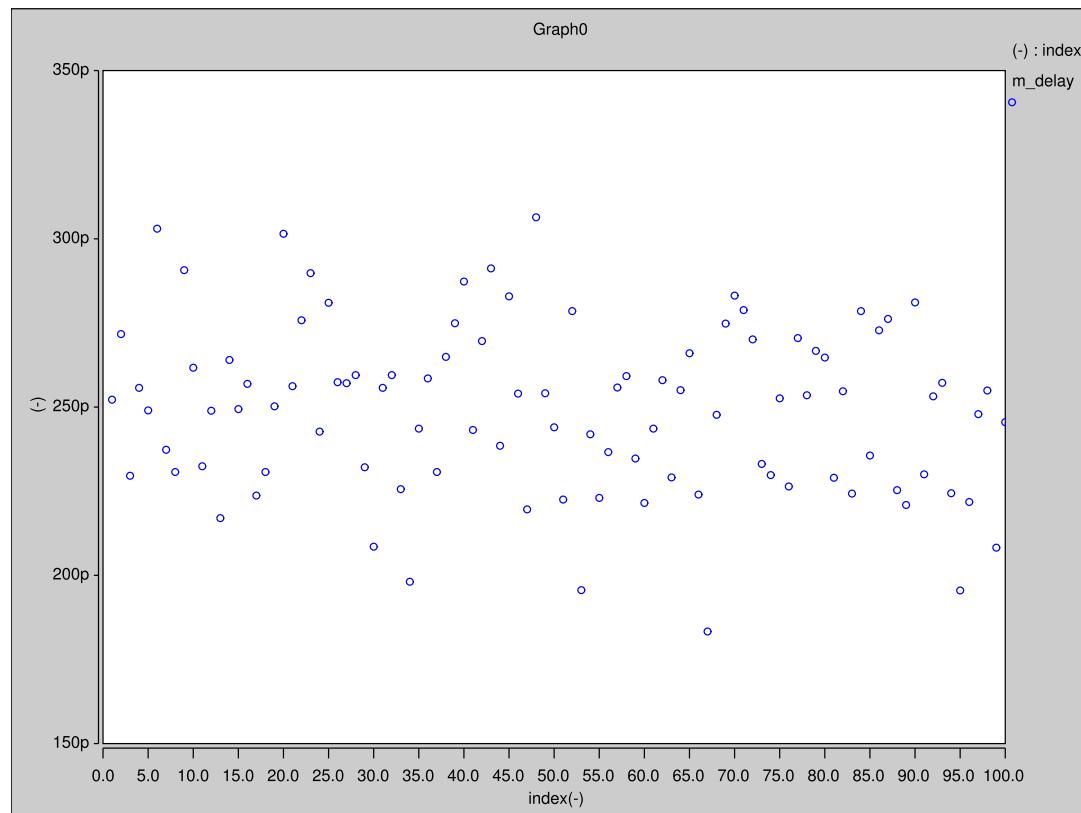
# INVERTER CHAIN DELAY AS FUNCTION OF SIGMA

- ◆ Varying sigma in all parameters,  $-3\sigma, -2.5\sigma, \dots, 2.5\sigma, 3\sigma$ .



# MONTE-CARLO SIMULATIONS

- ◆ In statistical simulations, each variable that follows the standard normal distribution is sampled randomly.



- ◆ Notice how the delay span reduces from 160ps-360ps.

## **CORNERS, SIGMA, AND MONTE CARLO**

- ◆ Simulations using process corners give pessimistic view of performance and power, but they have low run time.
- ◆ Monte Carlo simulation is the most accurate method, but it is very time consuming.

# **POWER, ENERGY AND VARIABILITY: CONCLUSION**

## ◆ Power and energy analysis.

- Depends on implementation, operating conditions and test vectors, thus, very complex.
- Combination of simulation and static analysis; identify where is the weakness in terms of accuracy. For example, do you need detailed implementation data if you have no use case information?

## ◆ Variability.

- Impacts delay and power dissipation.
- Simulation methods like Monte Carlo work only for small circuits.